

# PLATO PROBE SYSTEM

A Novel Langmuir Probe for Deposition Plasmas

<https://www.impedans.com/plato-probe>

# The Plato Probe System

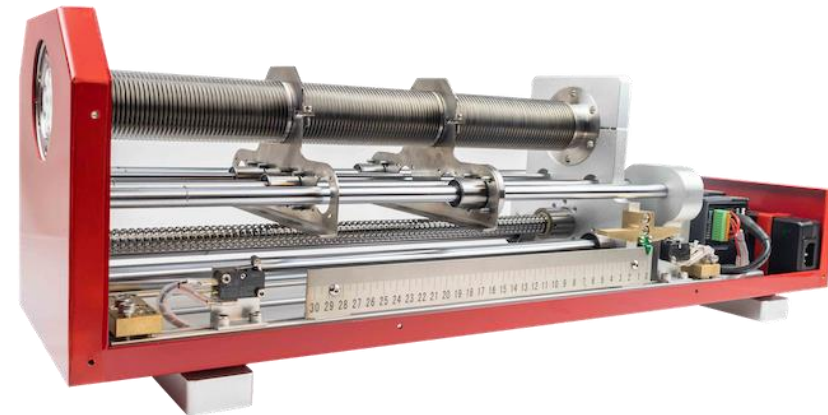
Measure the fundamental plasma parameters with the industry standard Langmuir Probe

## Parameters Measured:

- ✓ Ion Density
- ✓ Electron Temperature
- ✓ Parameters can be measured as a function of time (down to 1 microsecond resolution) or position

## Unique Planar Langmuir Probe:

- ✓ The Plato can take plasma measurements even when coated with insulating material up to 50 microns thick
- ✓ Accomplished using Octiv Suite technology
- ✓ The Octiv Suite data is processed using the Sobolewski method with compensation techniques of a Booth/Braithwaite probe



# Key Features

## Interchangeable probe heads



## Compatible with majority of plasma excitation methods

DC, pulsed DC, RF, pulsed RF, microwave and other plasma excitation methods.

## Integrated RF compensation filters

RF compensated up to 5 frequencies in one probe.

## Compatible with large deposition rates

Can tolerate up to 50 microns of an insulating layer and still measure plasma parameters



## Integrated linear drive mechanism

Linear drive mechanism provides automatic spatial plasma uniformity.

## Advanced software

State of the art plasma models built into software for automatic data analysis.

## External pulse synchronization

Time averaged, time trend, synchronized pulse profile and triggered fast-sweep modes.

## Intuitive and user friendly

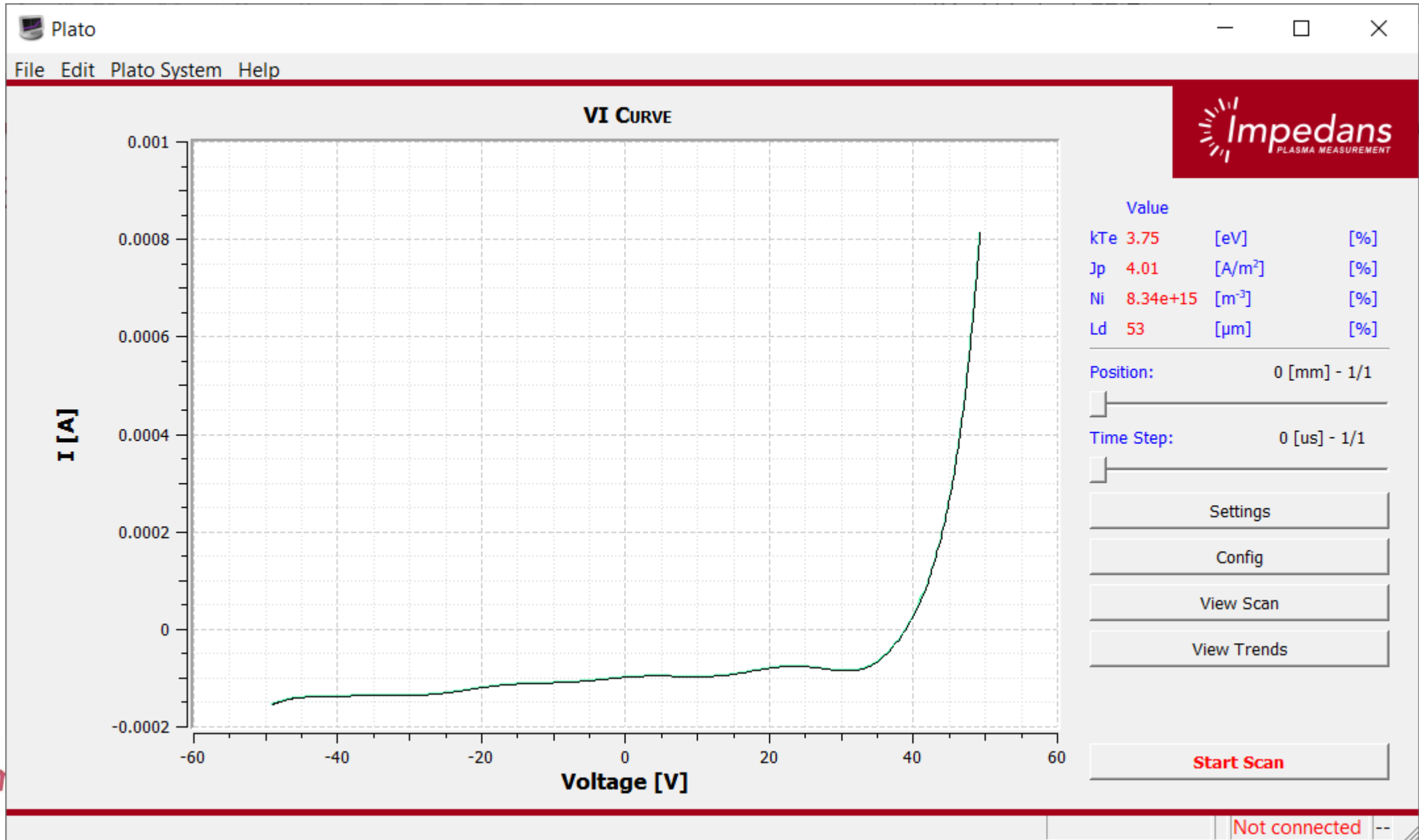
# Technical Specifications

Parameters Measured	Range
Voltage Scan Range	Floating Potential +/- 30 V
Current Range	300 $\mu A$ to 20 mA
Plasma Density	$10^8$ to $10^{13}$ $cm^{-3}$
Ion Current Density	26 $\mu A/cm^2$ to 300 mA/cm <sup>2</sup>
Electron Temperature	0.1 eV to 15 eV
TTL Sync for Pulsed Processes	10 Hz to 50 kHz
Time Resolved Step Resolution	1 $\mu s$
Maximum Operating Temperature	230 C
Plasma Power Source	DC, RF, Microwave, Continuous, Pulsed
RF Frequency Range	5 MHz to 100 MHz

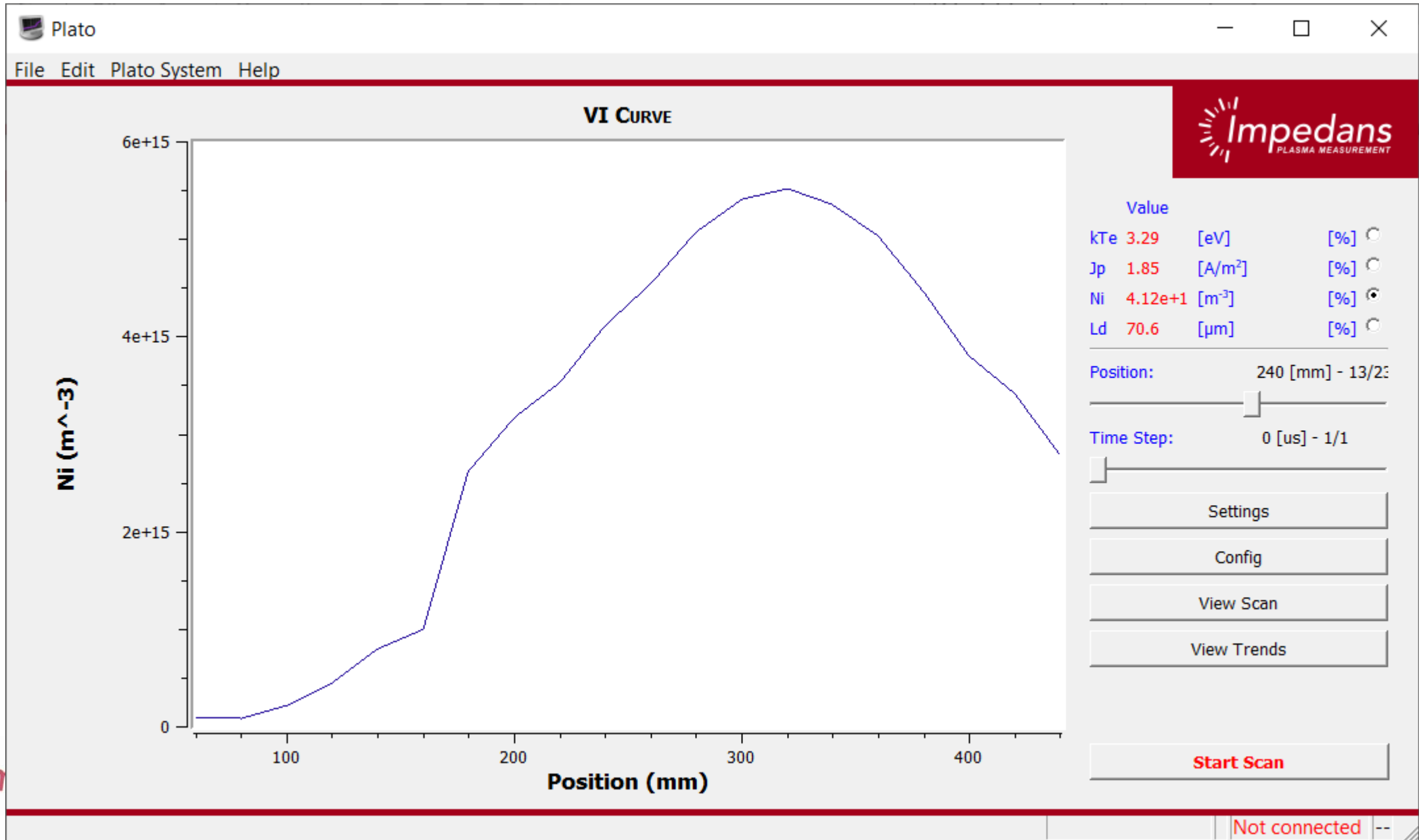
- ✓ For more detailed specifications and different models available, visit <https://impedans.com/plato-probe>
- ✓ To arrange a technical discussion, contact [support@impedans.com](mailto:support@impedans.com)



# Example Data: Typical VI curve



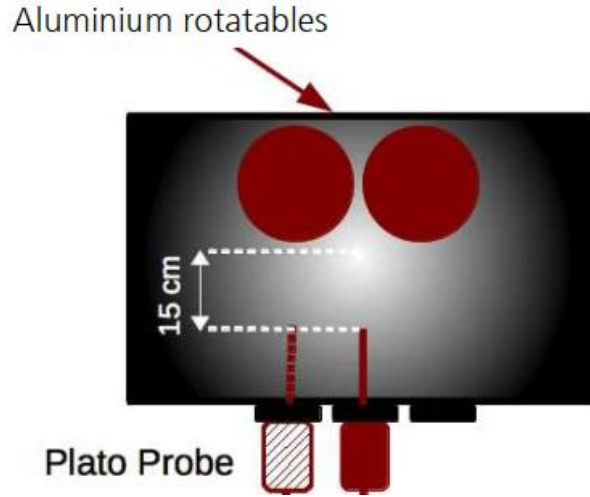
# Example Data: Ion Density vs Position



# Plato Applications

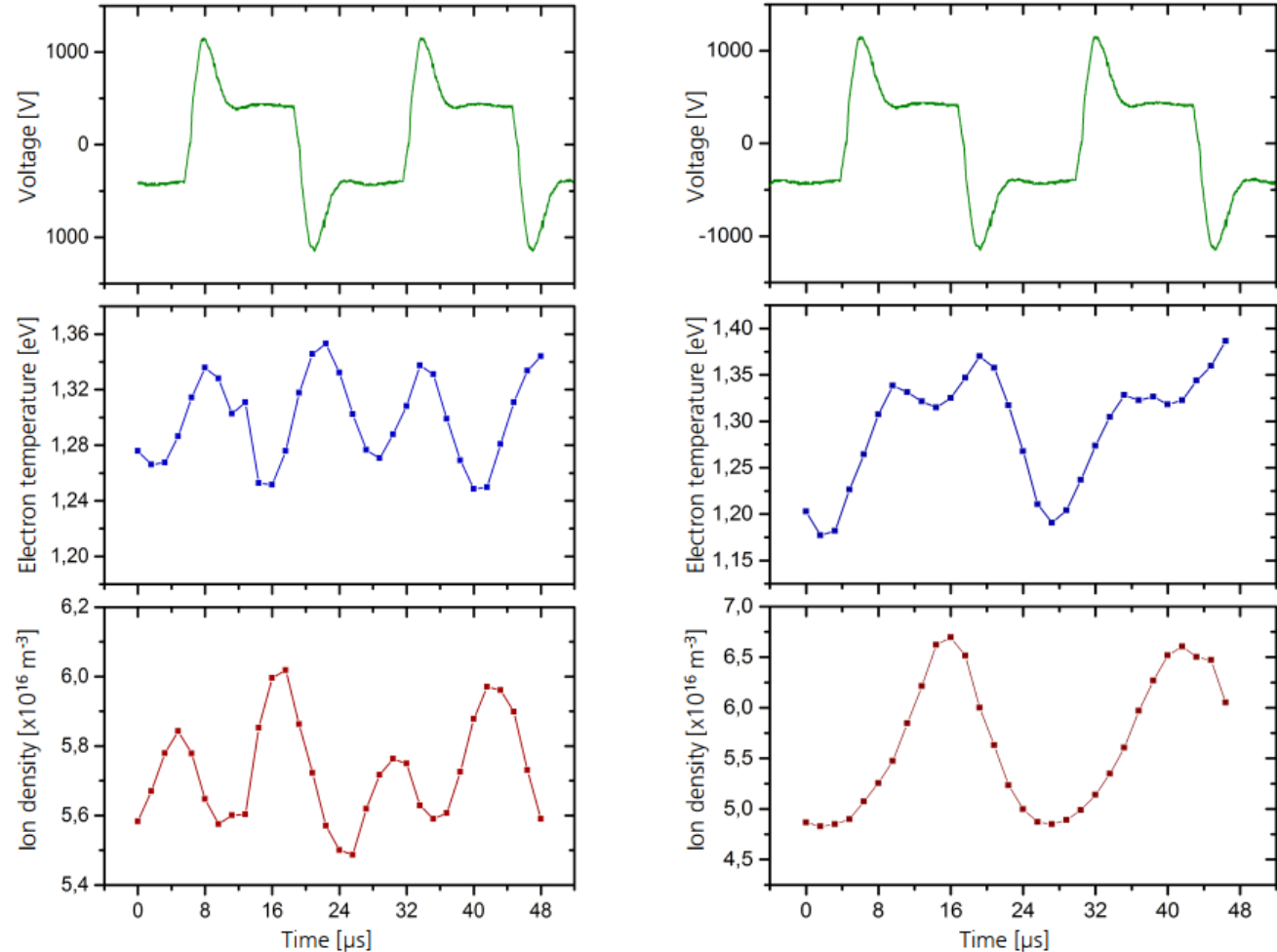
# Time-Resolved Measurements in a Dual-Magnetron Metal Process

## PLANAR LANGMUIR PROBE INVESTIGATIONS OF METALLIC AND REACTIVE BIPOLAR SPUTTERED ALUMINUM



The objective is to measure the plasma properties and thin film properties resulting in a dual magnetron source. Mid frequency excitation was used with 5 kW pulses and a 26  $\mu\text{s}$  period length.

Some example data is shown to the right

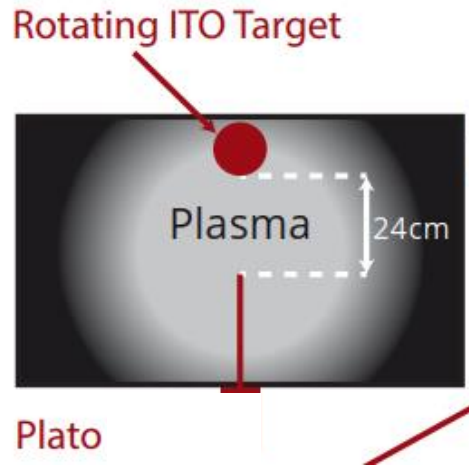


*Voltage, Electron Temperature and Ion Density measured between (left) and in front of (right) a dual magnetron rotatable source in metallic mode.*

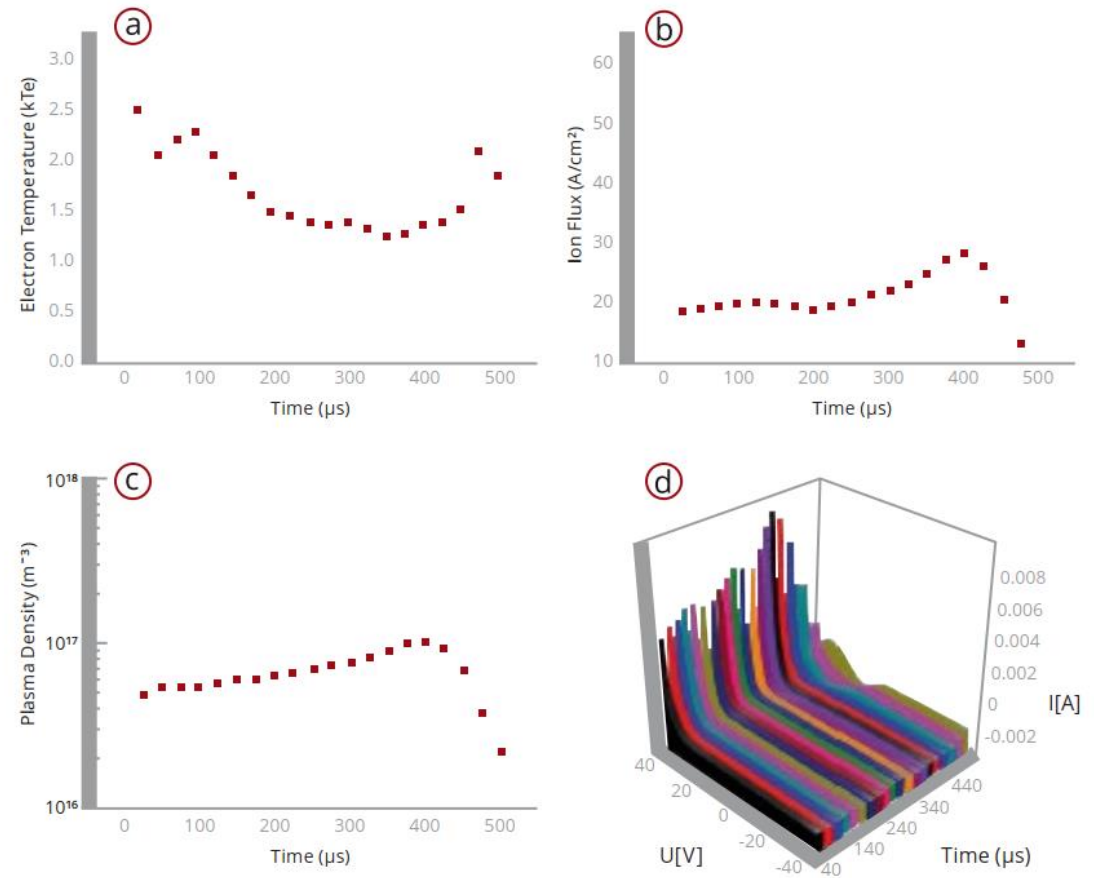


# Time-Resolved Measurements in a HiPIMS Process

## Characterization of HiPIMS plasma via process compatible measurement probe



This study looks at the characterization of a HiPIMS plasma using a process compatible plasma measurement probe which can be used in situations which require measurements at a fast time resolution, where in some cases the application may be depositing insulating layers.



Measurements of the plasma parameters in a 2 kHz process with a 450 us off time, 25 us acquisition step. Sputtering target was a iridium tin oxide cylinder.

# Plato Theory

# Plato Probe Equations

## Sobolewski Method:

$$I_{pe}(t) = -I_0 + I_e \text{Exp} \left[ \frac{V_{ps}(t)}{T_e} \right] + C_s(t) \frac{dV_{ps}}{dt}$$

## Booth & Braithwaite Method:

$$V_{probe,200} = V_{200 \text{ kHz}} - V_{C(200 \text{ kHz})}$$

$$V_{probe,400} = V_{400 \text{ kHz}} - V_{C(400 \text{ kHz})}$$

$$V_{C(200 \text{ kHz})} = I_{C(200 \text{ kHz})} X_{C(200 \text{ kHz})}$$

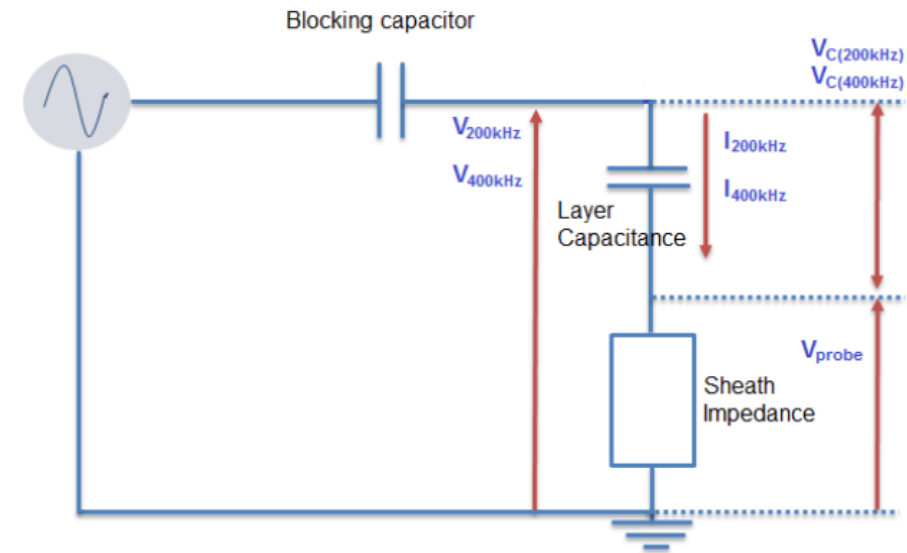
$$V_{C(400 \text{ kHz})} = I_{C(400 \text{ kHz})} X_{C(400 \text{ kHz})}$$

$$X_{C(200 \text{ kHz})} = \frac{2(V_{C(200 \text{ kHz})} - V_{C(400 \text{ kHz})})}{2I_{C(200 \text{ kHz})} - I_{C(400 \text{ kHz})}}$$

$$V_{probe} = V_{measured} - X_{C(200 \text{ kHz})}$$

## Ion Density:

$$n_i = \frac{I_{i,sat}}{A_p e} \sqrt{\frac{m_i}{kT_e}}$$



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